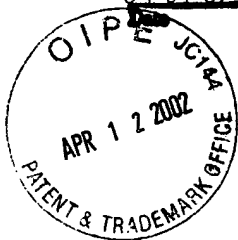


CERTIFICATE OF MAILING
I hereby certify that this paper and every
paper referred to therein as being enclosed
is deposited with the U.S. Postal Service
as first class mail, postage prepaid, in
an envelope addressed to: Assistant Commissioner
for Patents, Washington, D.C. 20231,
on APR 14, 2002 (Date of Deposit)
Shelly Ha
Name

Received



PATENT

Attorney Docket No. 306 D12
M&W Ref. No. APM/079-95-CP1-CN1-CPA-DV1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)	
COLLINS, ET AL.)	Group Art Unit: 1763
)	
Entitled: PLASMA REACTOR HAVING RF)	Examiner: Unknown
POWER APPLICATOR AND A DUAL-)	
PURPOSE WINDOW)	
)	
Serial No.: 10/021,195)	
)	
Filing Date: October 30, 2001)	

RECEIVED
APR 26 2002
TC 1700

REQUEST FOR CORRECTION OF FILING RECEIPT

Assistant Commissioner for Patents
OFFICE OF INITIAL PATENT EXAMINATION'S
CUSTOMER SERVICE CENTER
Washington, D.C. 20231

Dear Sir:

Applicants hereby request issuance of a new filing receipt to correct an error listed on the mailed from the USPTO on February 13, 2002. Please note the error highlighted on the enclosed copy of the Filing Receipt. In particular, the correction is listed as follows:

The Continuing Data as Claimed by Applicant is incomplete.
The Continuing Data does not list the complete prior history data as listed in the specification as filed. Enclosed please find a copy of the first two pages of the specification, as filed, listing the complete prior history data.

Applicants respectfully request the Patent Office to correct the Filing Receipt and forward copy to Applicant.

If the Examiner should have any questions regarding the above correction, the Examiner is requested to telephone Applicant's representative at the number listed below.

Respectfully submitted,



Robert M. Wallace

Reg. No. 29,119

Attorney for Applicant(s)

Dated: April 4, 2002

Please direct all telephone calls to:

Mr. Robert M. Wallace
Michaelson & Wallace
(805) 644-4035

Please continue to send all correspondence to:

Patent Counsel
Applied Materials, Inc.
P.O. Box 450-A
Santa Clara, CA 95035



APR 12 2002

UNITED STATES PATENT AND TRADEMARK OFFICE

COMMISSIONER FOR PATENTS
UNITED STATES PATENT AND TRADEMARK OFFICE
WASHINGTON, D.C. 20231
www.uspto.gov

APPLICATION NUMBER	FILING DATE	GRP ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLAIMS	IND CLAIMS
10/021,195	10/30/2001	1763	932	306 D12	26	26	4

COPY

CONFIRMATION NO. 1196

FILING RECEIPT



OC00000007468394

PATENT COUNSEL
APPLIED MATERIALS, INC.
Legal Department
3050 Bowers Ave., M/S#2061
Santa Clara, CA 95054

RECD FEB 20 2002

Date Mailed: 02/13/2002

Receipt is acknowledged of this nonprovisional Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Customer Service Center. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

Kenneth S. Collins, San Jose, CA;
Michael Rice, Pleasanton, CA;
Farahmand E. Askarinam, Sunnyvale, CA;
Douglas A. Buchberger JR., Tracy, CA;
Craig A. Roderick, San Jose, CA;

RECEIVED

APR 26 2002

TC 1700

Assignment For Published Patent Application

Applied Materials, Inc.;

Domestic Priority data as claimed by applicant

THIS APPLICATION IS A DIV OF 09/350,234 07/08/1999

Foreign Applications

If Required, Foreign Filing License Granted 02/12/2002

Projected Publication Date: 05/23/2002

Non-Publication Request: No

Early Publication Request: No

COMPUTER ENTERED

FEB 20 2002

Incomplete!!

Title

Plasma reactor having RF power applicator and a dual-purpose window

Preliminary Class

216

**LICENSE FOR FOREIGN FILING UNDER
Title 35, United States Code, Section 184
Title 37, Code of Federal Regulations, 5.11 & 5.15**

GRANTED

The applicant has been granted a license under 35 U.S.C. 184, if the phrase "IF REQUIRED, FOREIGN FILING LICENSE GRANTED" followed by a date appears on this form. Such licenses are issued in all applications where the conditions for issuance of a license have been met, regardless of whether or not a license may be required as set forth in 37 CFR 5.15. The scope and limitations of this license are set forth in 37 CFR 5.15(a) unless an earlier license has been issued under 37 CFR 5.15(b). The license is subject to revocation upon written notification. The date indicated is the effective date of the license, unless an earlier license of similar scope has been granted under 37 CFR 5.13 or 5.14.

This license is to be retained by the licensee and may be used at any time on or after the effective date thereof unless it is revoked. This license is automatically transferred to any related applications(s) filed under 37 CFR 1.53(d). This license is not retroactive.

The grant of a license does not in any way lessen the responsibility of a licensee for the security of the subject matter as imposed by any Government contract or the provisions of existing laws relating to espionage and the national security or the export of technical data. Licensees should apprise themselves of current regulations especially with respect to certain countries, of other agencies, particularly the Office of Defense Trade Controls, Department of State (with respect to Arms, Munitions and Implements of War (22 CFR 121-128)); the Office of Export Administration, Department of Commerce (15 CFR 370.10 (j)); the Office of Foreign Assets Control, Department of Treasury (31 CFR Parts 500+) and the Department of Energy.

NOT GRANTED

No license under 35 U.S.C. 184 has been granted at this time, if the phrase "IF REQUIRED, FOREIGN FILING LICENSE GRANTED" DOES NOT appear on this form. Applicant may still petition for a license under 37 CFR 5.12, if a license is desired before the expiration of 6 months from the filing date of the application. If 6 months has lapsed from the filing date of this application and the licensee has not received any indication of a secrecy order under 35 U.S.C. 181, the licensee may foreign file the application pursuant to 37 CFR 5.15(b).



COPY

1

Attorney Docket No. 306 D12

PLASMA REACTOR HAVING RF POWER APPLICATOR AND A DUAL-PURPOSE WINDOW

Inventors: Kenneth S. Collins, Michael Rice, Farahmand E. Askarinam, Douglas A. Buchberger, Jr., Craig A. Roderick

BACKGROUND OF THE INVENTION

Technical Field:

The invention is related to heating and cooling apparatus in an inductively coupled RF plasma reactors of the type having a reactor chamber ceiling overlying a workpiece being processed and an inductive coil antenna adjacent the ceiling.

Related Applications:

This application is a divisional of U.S. Patent application Serial No. 09/350,234, filed July 9, 1999 entitled "Plasma Reactor Having A Dual Mode RF Power Application" (currently pending), which is a continuation of application Serial No. 08/733,555, filed October 1, 1996 (now issued as Patent No. 6,063,233), which is a continuation-in-part of application Serial No. 08/648,254, filed May 13, 1996 (now issued as Patent No. 6,165,311), which is a continuation-in-part of application Serial No. 08/580,026, filed December 20, 1995 (currently pending), which is a continuation of application Serial No. 08/041,796, filed April 1, 1993 (now abandoned), which is a continuation of application Serial No. 07/722,340, filed June 27, 1991 (now abandoned), which is a continuation-in-part of application Serial No. 08/503,467, filed July 18, 1995 (now issued as Patent No. 5,770,099), which is a

RECEIVED
APR 26 2002
TC 1700

divisional of application Serial No. 08/138,060, filed October 15, 1993 (now issued as Patent No. 5,477,975), which is a continuation-in-part of application Serial No. 08/597,577, filed February 2, 1996 (now issued as Patent No. 6,077,384), which is a continuation-in-part of application Serial No. 08/521,668, filed August 31, 1995 (now abandoned), which is a continuation-in-part of application Serial No. 08/289,336, filed August 11, 1994 (now abandoned), which is a continuation of application Serial No. 07/984,045, filed December 1, 1992 (now abandoned). In addition, U.S. application Serial No. 08/648,265 filed May 13, 1996 (now issued as Patent No. 6,165,311) discloses related subject matter.

15 Background Art:

In a plasma processing chamber, and especially in a high density plasma processing chamber, RF (radio frequency) power is used to generate and maintain a plasma within the processing chamber. As disclosed in detail in the above-referenced applications, it is often necessary to control temperatures of surfaces within the process chamber, independent of time varying heat loads imposed by processing conditions, or of other time varying boundary conditions. In some cases where the window/electrode is a semiconducting material, it may be necessary to control the temperature of the window/electrode within a temperature range to obtain the proper electrical properties of the window. Namely, for the window/electrode to function simultaneously as a window and as an electrode, the electrical resistivity is a function of temperature for semiconductors, and the temperature of the window/electrode is best operated within a range of temperatures. The application of RF power to